PATENT APPLICATION Do. No. 5484-48

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Byung-Sup SHIM et al.

Serial No.

09/305,240

Examiner:

O. Nadav

Filed:

May 4, 1999

Group Art Unit:

2811

For:

OPEN DRAIN INPUT/OUTPUT STRUCTURE AND

MANUFACTURING METHOD THEREOF IN SEMICONDUCTOR

**DEVICE** 

Box CPA

**Assistant Commissioner for Patents** 

Washington, D.C. 20231

## PRELIMINARY AMENDMENT

Prior to examination, please amend the application as follows

## **IN THE SPECIFICATION**

On page 2, line 25, replace "FIG.s" with --FIGs.--;

On page 4, line 9, replace "a n-type" with -- an n-type--.

## **IN THE CLAIMS**:

Please amend claim 2 as follows:

9. The transistor of claim 5, wherein the first sector (Twice Amended) is separated from the source region and from the drain region by substantially equal distances.

## **REMARKS**

In this case, a Final Office Action was mailed on 8-31-2000. All pending claims [namely 5-7, 9] were rejected.

MJM DO. NO. 5484-48